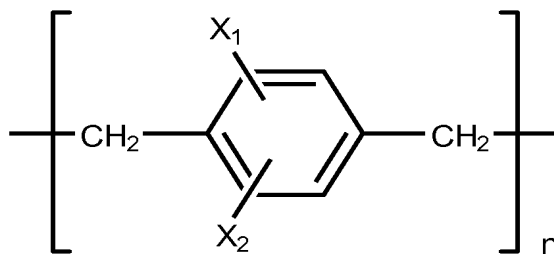


ABSTRACT

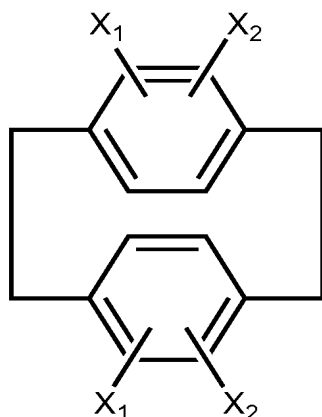
A method for improving the heat stability of polyparaxylylene and a derivative film thereof to improve the heat resistance of the polyparaxylylene and the derivative film thereof without deteriorating deposition characteristics or profitability, and a polyparaxylylene derivative whose heat resistance is improved are provided. When the polyparaxylylene or the derivative film thereof represented by a below-described general formula 1 is formed by a chemical vapor deposition method, an amino-(2.2)-paracyclophane compound represented by a below-described general formula 3 is mixed in a (2.2)-paracyclophane compound represented by a below-described general formula 2 to form a film.

General formula 1



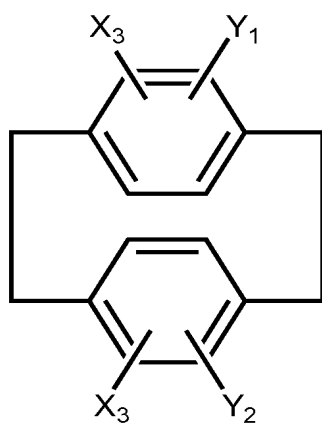
(In the formula 1, X_1 and X_2 designate hydrogen, lower alkyl or halogen. X_1 and X_2 may be the same or different. n represents a degree of polymerization.)

General formula 2



(In the formula 2, X_1 and X_2 have the same meanings as those of the formula 1.)

General formula 3



(In the formula 3, X_3 designates hydrogen or a lower alkyl group. Y_1 and Y_2 designate hydrogen or an amino group and both Y_1 and Y_2 are not hydrogens at the same time.)